

Extension of the Dynamic Range using the Switching Operation of In-Pixel Inverter in Complementary Metal Oxide Semiconductor Image Sensors

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Abstract

This paper proposes the extension of the dynamic range in complementary metal oxide semiconductor (CMOS) image sensors (CIS) using switching operation of in-pixel inverter. A CMOS inverter is integrated in each unit pixel of the proposed CIS for switching operations. The n+/p-substrate photodiode junction capacitances are added to each unit pixel. When the output voltage of the photodiode is less than half of the power supply voltage of the CMOS inverter, the output voltage of the CMOS inverter changes from 0 V to the power supply voltage. Hence, the output voltage of the CMOS inverter is adjusted by changing the supply voltage of the CMOS inverter. Thus, the switching point is adjusted according to light intensity when the supply voltage of the CMOS inverter changes. Switching operations are then performed because the CMOS inverter is integrated with in each unit pixel. The proposed CIS is composed of a pixel array, multiplexers, shift registers, and biasing circuits. The size of the proposed pixel is 10 $\mu\text{m} \times 10 \mu\text{m}$. The number of pixels is 150 (H) \times 220 (V). The proposed CIS was fabricated using a 0.18 μm 1-poly 6-metal CMOS standard process and its characteristics were experimentally analyzed.

Keywords: CMOS image sensor, Dynamic range extension, CMOS inverter, Switching operation, Sensitivity, Junction capacitance

1. INTRODUCTION

Complementary metal oxide semiconductor (CMOS) image sensors (CIS) are used for camera applications, such as security cameras, webcam, and camcorders. CIS have several advantages over charge-coupled device (CCD) image sensors, including low power consumption, low cost, and compatibility with standard CMOS technology [1-2]. CIS are evaluated by considering their characteristics such as dynamic range, resolution, and power consumption. In this paper, we propose a dynamic range extension of CIS using switching operation of in-pixel inverter. The dynamic range is defined as the ratio between the full-well capacity and the floor noise. To extend the dynamic range of CIS, several techniques have been proposed [3-9]. Although they succeeded in achieving wide dynamic range, these techniques

have their disadvantages as well. For example, a CIS having characteristics of linear-logarithmic response was proposed [3]. The logarithmic active pixel sensor (APS) has excessive dynamic range. However, in logarithmic APS, fixed pattern noise (FPN) is a major problem because FPN is generated due to hot-carrier-induced threshold voltage shift in the logarithmic APS. Additionally, the multiple sampling technique was proposed [4]. The multiple sampling technique also achieves a wide dynamic range by synthesizing different exposure time images.

However, a fast-moving object captured as an image is subject to image distortion. In a previous work, wide dynamic range CIS with adjustable sensitivity using a cascade metal-oxide semiconductor field-effect transistor (MOSFET) and an inverter was proposed [5]. The logarithmic response was used to extend the dynamic range using in-pixel inverter. In this research, it was observed that dynamic range extension is achieved by linearly changing the sensitivity of the pixel unit. The characteristics of the proposed CIS were evaluated using measurements. Thus, a dynamic range extension using a CMOS inverter in the unit pixel is proposed. According to the intensity of light incident on the proposed APS, it is possible to verify whether the CMOS inverter is in operation. When the CMOS inverter is turned on, the dynamic range of the proposed CIS is extended. On the other hand, when the CMOS inverter is off, the proposed CIS is

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operated in the conventional mode as switching operation is not performed.

2. DESIGN AND OPERATING PRINCIPLE

2.1 Design of unit pixel

In this research, the dynamic range extension of CIS via the switching operation of in-pixel inverter using CMOS inverter, which is integrated in each pixel unit, is presented. The proposed unit pixel is based on the photodiode-type APS [10]. Fig. 1 shows the schematic diagram of the proposed unit pixel. The CMOS inverter (M6, M7), additional reset transistor (M1), switch transistor (M5), and n+/p-substrate (n+/p-sub) junction capacitances are included along with the unit pixel. In the proposed CIS, Node A in Fig. 1 shows the input node of the CMOS inverter which is equal to the input node of the source follower (M3). Node B shows the output node of the CMOS inverter connected to the gate of the M5 transistor. Two reset transistors (M1, M2) are used for the reset operation to deplete the electrons accumulated at the n+/p-sub junction. Finally, the selected transistor M4 is used to estimate the pixel output voltage V_{OUT} .

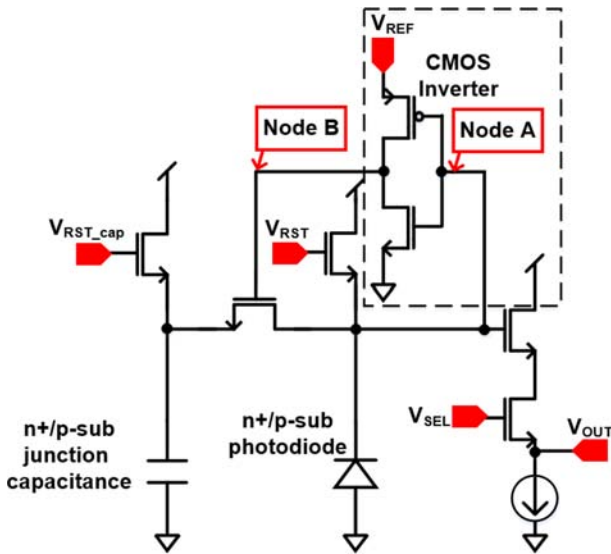


Fig. 1. Schematic diagram of the proposed unit pixel.

In Fig. 2, the cross-sectional view of the proposed unit pixel is shown. It was proved previously that signal electrons are generated when the reverse-biased n+/p-sub junction photodiode is exposed to light [11]. On the other hand, a metal layer located on the upper side of the junction capacitance blocks the light, hence avoiding the exposure of the n+/p-sub junction capacitance. The n+/p-sub

junction capacitances are included for storing the signal electrons rather than generating them. Polycrystalline silicon (poly-Si) gates separate the light-receiving and electron-storage areas which comprise the n+/p-sub junction. The input gate of the CMOS inverter is connected to the n+ region of the light-receiving area. The output node of the CMOS inverter is connected to the poly-Si gates to apply the switching operation according to light intensity.

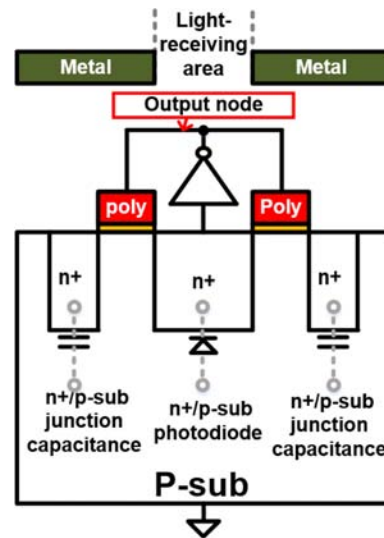


Fig. 2. Cross-sectional view of the proposed unit pixel.

2.2 Operating principle

To operate the proposed CIS, additional reset operations are used to deplete the electrons stored in the additional n+/p-sub capacitances. These additional reset operations have to be added to the operation of conventional 3-Tr APS. In the schematic of the APS described in Fig. 1, the additional reset transistor (M1) can set the value of voltage for the initial condition before the exposure time. When the signal voltage at the n+ region of the photodiode is changed, the output voltage of the CMOS inverter changes from 0 V to V_{REF} based on the $V_{REF}/2$ voltage. Subsequently, the n+/p-sub junction capacitances are connected to the n+/p-sub photodiodes. Thus, the capacitance of the n+/p-sub photodiode increases and the sensitivity of the proposed pixel decreases. V_{REF} of the M6 transistor is the supply voltage of the CMOS inverter, which can be adjusted to change the switching point.

In Fig. 3, the timing diagram of the proposed method for dynamic range extension is shown. First, reset operations are performed to eliminate the signal electrons in the n+/p-sub junction. Subsequently, the signal voltage changes when signal electrons are generated at the n+/p-sub photodiode due to exposure to light. During the exposure time, when the input

voltage of the CMOS inverter is below $V_{REF}/2$, the output voltage of the CMOS inverter changes from 0 V to V_{REF} [12]. When the CMOS inverter is turned on, the switching operation is complete and the sensitivity of the unit pixel decreases since the n+/p-sub junction capacitances are connected to the n+/p-sub photodiode. Finally, dynamic range extension is performed by the switching operation of the CMOS inverters located in each unit pixel. Hence, the dynamic range extension is automatically performed at each unit pixel using the CMOS inverter.

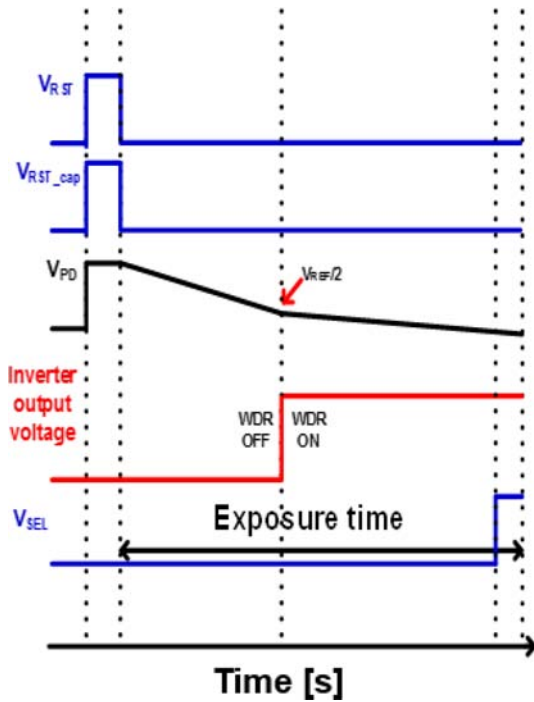


Fig. 3. Timing diagram for the operation of the proposed method of dynamic range extension.

3. RESULTS AND DISCUSSIONS

3.1 Measurement results

Several measurements were performed to verify the dynamic range extension of CIS using the switching operation of in-pixel inverter. Fig. 4 shows, the comparison of the pixel output voltage characteristics as a function of the light intensity in the conventional and WDR modes. When V_{REF} is 0 V, the CMOS inverter is turned off during the exposure since the supply voltage is not applied to the CMOS inverter. On the other hand, when V_{REF} is applied to the supply voltage of the CMOS inverter, the switching operation is performed in accordance with the light intensity. After the switching operation, the switch is turned by the output voltage of the CMOS inverter, causing the switch in each unit pixel to turn on.

Subsequently, additional capacitances are attached to the photodiode to decrease the sensitivity of the unit pixel. Fig. 4 shows that the switching operation is performed at around 1,000 lux light exposure and the dynamic range is extended.

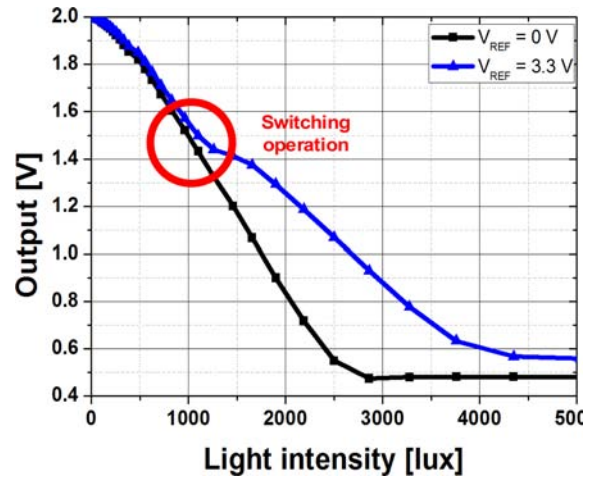


Fig. 4. Comparison of pixel output voltage characteristics as a function of the light intensity between the conventional mode and the wide dynamic range mode.

Fig. 5 shows, the pixel output voltage characteristics as a function of the supply voltage of the CMOS inverter. Changing the supply voltage of the CMOS inverter changes, the switching point. In other words, the switching point is adjusted by changing the V_{REF} voltage. When V_{REF} is 0 V, the sensitivity is unchanged as the CMOS inverter is turned off and the additional capacitances are not connected to the n+/p-sub photodiode. In contrast, when V_{REF} is 1.8 V, 2.7 V, or 3.3 V, the switching point is adjusted individually as the CMOS inverter is turned on at different times.

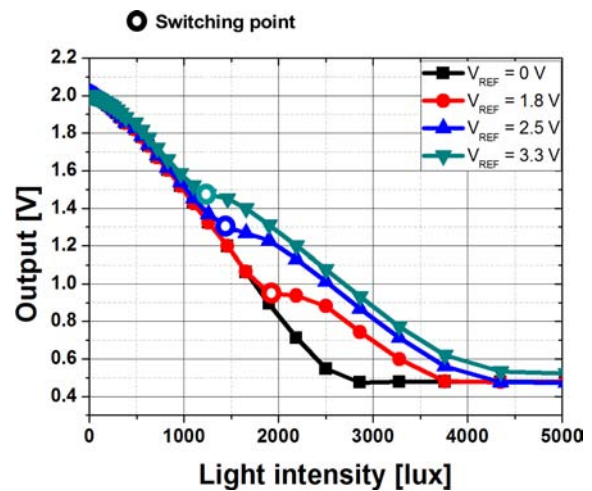


Fig. 5. Pixel output voltage characteristics according to power supply voltage of in-pixel CMOS inverter.

Table 1 shows the characteristics of the proposed CIS, which was fabricated by the 1-poly 6-metal 0.18 μm standard CMOS process. The supply voltage is 3.3 V for analog circuits and 1.8 V for digital circuits. The resolution is 150 (H) \times 220 (V) with a 100 μm^2 unit pixel pitch. The fill factor is 20.9 %. The dynamic range of the WDR mode operation is extended by 4 dB more than that of the conventional mode operation using the switching operation of the CMOS inverter.

Table 1. Characteristics of the proposed CMOS image sensor.

Parameter	Value
Technology	1-poly 6-metal 0.18 μm CMOS process
Resolution	150 (H) \times 220 (V)
Power supply	Analog : 3.3 V, Digital : 1.8 V
Pixel pitch	10 μm \times 10 μm
Dynamic range	Conventional mode : approximately 25 dB WDR mode : approximately 29 dB

Fig. 6 shows the captured images for different values of V_{REF} supply voltage of the CMOS inverter integrated at each unit pixel. When V_{REF} is 0 V, the image of objects located in the front is saturated when the light intensity is high. On the other hand, when the V_{REF} is changed to 3.3 V, the dynamic range is extended owing to the switching operation of the in-pixel CMOS inverter. Comparing the images in Fig. 6 (a) and (b), it is evident that using the CMOS inverter extends the dynamic range.

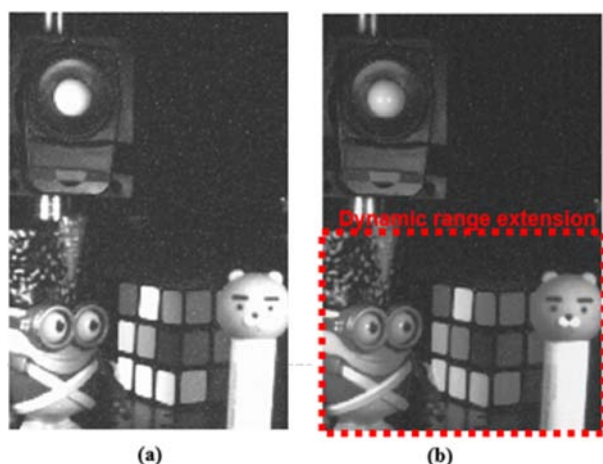


Fig. 6. Captured images when V_{REF} is (a) 0 V, and (b) 3.3 V.

3.2 Discussions

In the proposed CIS, the CMOS inverter is integrated in each unit pixel. The fill factor of the unit pixel decreases because additional transistors, such as the CMOS inverter, are integrated in

each unit pixel. To increase the fill factor of the unit pixel, the size of the transistors in the CMOS inverter needs to be optimized. In other words, when the minimum length of the MOSFET gate shortens, the size of transistors in a CMOS inverter can be minimized.

It is evident that the automatic operation to change the sensitivity during the exposure time can be used for WDR operation. The proposed CIS has the advantage of an automatic wide dynamic range operation based on light intensity. The WDR operation is performed according to the light intensity using the proposed unit pixel structure without changing the readout circuits. In the unit pixel, the additional n+/p-sub junction capacitance is included, whose value can be applied differently. When this value increases, the sensitivity decreases after the switching operation.

Fig. 7 shows the results of the simulation of pixel output voltage characteristics according to the value of the n+/p-sub junction capacitance. The value of the n+/p-sub junction capacitance in each pixel are 10 fF, 30 fF, 50 fF, 70 fF, and 90 fF. Post the switching operation, the sensitivity of the unit pixel is dependent on the value of n+/p-sub junction capacitance.

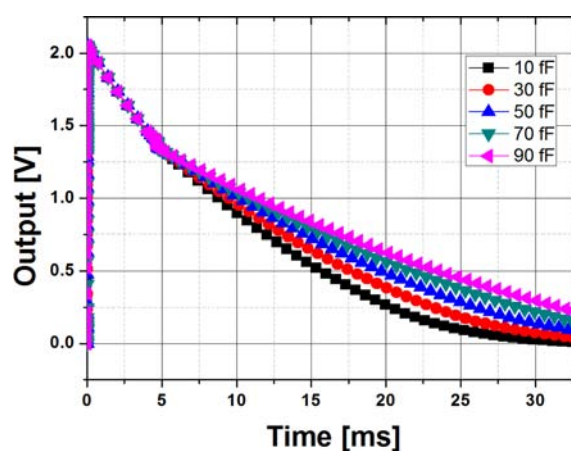


Fig. 7. Simulation results of pixel output voltage characteristics according to the value of n+/p-sub junction capacitance.

4. CONCLUSIONS

Extension of the dynamic range using the switching operation of in-pixel inverter in CIS has been presented. The proposed CIS consists of a pixel array, multiplexers, shift registers, and biasing circuits. It is possible that the WDR mode or conventional mode is operated using the switching operation of in-pixel inverter according to the light intensity. The proposed CIS was fabricated using the 0.18 μm 1-poly 6-metal CMOS standard process.

Experiments were carried out to evaluate the characteristics of the proposed CIS. When the output of the CMOS inverter changes from 0 V to V_{REF} , the sensitivity of the proposed pixel decreases as compared to the sensitivity of the unit pixel in the conventional mode. The in-pixel inverter was used to decrease the sensitivity of the unit pixel in the WDR mode of operation. As a result, the proposed CIS can be used for the dynamic range extension of CIS to acquire the images under various light conditions.

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